

# Kuan Eng J Goh

## List of Publications by Year in descending order

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82  
papers

2,138  
citations

236833

25  
h-index

254106

43  
g-index

86  
all docs

86  
docs citations

86  
times ranked

2989  
citing authors





#	ARTICLE	IF	CITATIONS
37	Band Engineering of the Si(001):H Surface by Doping with P and B Atoms. <i>Advances in Atom and Single Molecule Machines</i> , 2017, , 95-104.	0.0	0
38	Nanoscale characterization of oxidized ultrathin Co-films by ballistic electron emission microscopy. <i>Materials Research Express</i> , 2016, 3, 015001.	0.8	0
39	Electrically-Excited Surface Plasmon Polaritons with Directionality Control. <i>ACS Photonics</i> , 2015, 2, 385-391.	3.2	34
40	Electronically Transparent Graphene Barriers against Unwanted Doping of Silicon. <i>ACS Applied Materials &amp; Interfaces</i> , 2014, 6, 20464-20472.	4.0	17
41	Low temperature nanoscale electronic transport on the MoS <sub>2</sub> surface. <i>Applied Physics Letters</i> , 2013, 103, .	1.5	16
42	Dangling-Bond Wire Circuits on a Si(001)-(2x1):H Surface with Their Contacting Nanopads. <i>Advances in Atom and Single Molecule Machines</i> , 2013, , 163-174.	0.0	0
43	Patterning of sub-1 nm dangling-bond lines with atomic precision alignment on H:Si(100) surface at room temperature. <i>Nanotechnology</i> , 2012, 23, 275301.	1.3	11
44	Barrier height determination of Au/Oxidized GaAs/n-GaAs using ballistic electron emission spectroscopy. <i>Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics</i> , 2012, 30, .	0.6	2
45	Effect of surface contamination on electron tunneling in the high bias range. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012, 30, 041402.	0.9	3
46	Temperature-dependent relaxation current on single and dual layer Pt metal nanocrystal-based Al <sub>2</sub> O <sub>3</sub> /SiO <sub>2</sub> gate stack. <i>Journal of Applied Physics</i> , 2012, 112, 104503.	1.1	1
47	Subthreshold characteristics of ballistic electron emission spectra. <i>Journal of Applied Physics</i> , 2012, 111, .	1.1	7
48	The electronic barrier height of silicon native oxides at different oxidation stages. <i>Journal of Applied Physics</i> , 2012, 111, .	1.1	2
49	Study of the charge leakage of dual layer Pt metal nanocrystal-based high- $\kappa$ Al <sub>2</sub> O <sub>3</sub> /SiO <sub>2</sub> flash memory cell - a relaxation current point of view. , 2011, , .		0
50	Electronic properties of ultrathin high- $\kappa$ dielectrics studied by ballistic electron emission microscopy. <i>Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics</i> , 2011, 29, .	0.6	3
51	Study of automatic recovery on the metal nanocrystal-based Al <sub>2</sub> O <sub>3</sub> /SiO <sub>2</sub> gate stack. <i>Applied Physics Letters</i> , 2011, 98, .	1.5	0
52	Using patterned H-resist for controlled three-dimensional growth of nanostructures. <i>Applied Physics Letters</i> , 2011, 98, .	1.5	9
53	Tri-Level Resistive Switching in Metal-Nanocrystal-Based Al <sub>2</sub> O <sub>3</sub> /SiO <sub>2</sub> Gate Stack. <i>IEEE Transactions on Electron Devices</i> , 2010, 57, 3001-3005.	1.6	7
54	Dual parameter ballistic electron emission spectroscopy analysis of inhomogeneous interfaces. <i>Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics</i> , 2010, 28, C5F1-C5F4.	0.6	5

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55	Ballistic Electron Emission Microscopy on Hybrid Metal/Organic/Semiconductor Interfaces. , 2010, , 57-73.		0
56	Impact of Si growth rate on coherent electron transport in Si:P delta-doped devices. Applied Physics Letters, 2009, 95, 142104.	1.5	11
57	Electrostatic effects of nanoscale dielectric patches in the modification of Schottky contacts. Physical Review B, 2009, 79, .	1.1	6
58	Atomic-scale silicon device fabrication. International Journal of Nanotechnology, 2008, 5, 352.	0.1	28
59	Imaging buried organic islands by spatially resolved ballistic electron emission spectroscopy. Nanotechnology, 2008, 19, 445718.	1.3	16
60	Enhancing electron transport in Si:P delta-doped devices by rapid thermal anneal. Applied Physics Letters, 2008, 93, 142105.	1.5	13
61	Electron-electron interactions in highly disordered two-dimensional systems. Physical Review B, 2008, 77, .	1.1	40
62	Ohmic conduction of sub-10nm P-doped silicon nanowires at cryogenic temperatures. Applied Physics Letters, 2008, 92, 052101.	1.5	12
63	Morphology and electrical conduction of Si:P $\hat{\Gamma}$ -doped layers on vicinal Si(001). Journal of Applied Physics, 2008, 104, 066104.	1.1	10
64	Comparison of GaP and PH <sub>3</sub> as dopant sources for STM-based device fabrication. Nanotechnology, 2007, 18, 065301.	1.3	8
65	Atomically precise silicon device fabrication. , 2007, , .		1
66	Use of a scanning electron microscope to pattern large areas of a hydrogen resist for electrical contacts. Journal of Applied Physics, 2007, 102, .	1.1	8
67	Use of low-temperature Hall effect to measure dopant activation: Role of electron-electron interactions. Physical Review B, 2007, 76, .	1.1	6
68	Electronic properties of atomically abrupt tunnel junctions in silicon. Physical Review B, 2007, 75, .	1.1	31
69	One-dimensional conduction properties of highly phosphorus-doped planar nanowires patterned by scanning probe microscopy. Physical Review B, 2007, 76, .	1.1	33
70	Narrow, highly P-doped, planar wires in silicon created by scanning probe microscopy. Nanotechnology, 2007, 18, 044023.	1.3	24
71	Bilayer gate dielectric study by scanning tunneling microscopy. Applied Physics Letters, 2007, 91, 102905.	1.5	38
72	Electrical properties of atomically controlled Si:P nanowires created by scanning probe microscopy. AIP Conference Proceedings, 2007, , .	0.3	0

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73	Realization of Atomically Controlled Dopant Devices in Silicon. <i>Small</i> , 2007, 3, 563-567.	5.2	108
74	Influence of doping density on electronic transport in degenerate Si:P <sup>+</sup> -doped layers. <i>Physical Review B</i> , 2006, 73, .	1.1	62
75	The fabrication of devices in silicon using scanning probe microscopy. , 2005, , .		0
76	Relevance of phosphorus incorporation and hydrogen removal for Si:P <sup>+</sup> -doped layers fabricated using phosphine. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2005, 202, 1002-1005.	0.8	10
77	The use of etched registration markers to make four-terminal electrical contacts to STM-patterned nanostructures. <i>Nanotechnology</i> , 2005, 16, 2446-2449.	1.3	26
78	Effective removal of hydrogen resists used to pattern devices in silicon using scanning tunneling microscopy. <i>Applied Physics Letters</i> , 2005, 86, 143116.	1.5	11
79	Scanning probe microscopy for silicon device fabrication. <i>Molecular Simulation</i> , 2005, 31, 505-515.	0.9	50
80	Effect of encapsulation temperature on Si:P <sup>+</sup> -doped layers. <i>Applied Physics Letters</i> , 2004, 85, 4953-4955.	1.5	44
81	Toward Atomic-Scale Device Fabrication in Silicon Using Scanning Probe Microscopy. <i>Nano Letters</i> , 2004, 4, 1969-1973.	4.5	150
82	Minimisation of P surface segregation during epitaxial silicon growth for the fabrication of a silicon-based quantum computer. , 0, , .		0